



State-of-the-Art of Optical Micro/Nano-Metrology and Instrumentation

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Message from the Guest Editors

Dear Colleagues,

State-of-the-art optical micro/nano-metrology in the manufacturing industry can be classified into two groups according to their main uses: those used for precision positioning, such as all kinds of optical sensors for linear and angular displacement measurement, and those used for quality assessment of products, such as interferometry, deflectometry, diffractometry and scatterometry for surface form or texture measurement, as well as optical coherence tomography for internal structure inspection.

This Special Issue welcomes any papers about state-of-art optical micro/nano-metrology and instrumentation for precision positioning or quality assessment of products in manufacturing processes. The recent progress revealing novel optical measurement technologies and instrumentations in dealing with the new requirements and challenges with the advent of new processing technologies is also expected in this Special Issue.

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Message from the Editor-in-Chief

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